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(54) **MANUFACTURING METHOD FOR LINEAR-GRID OF DISPLAY PANEL**

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G03F 7/00	(2006.01)
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(58) **Field of Classification Search**

None

See application file for complete search history.

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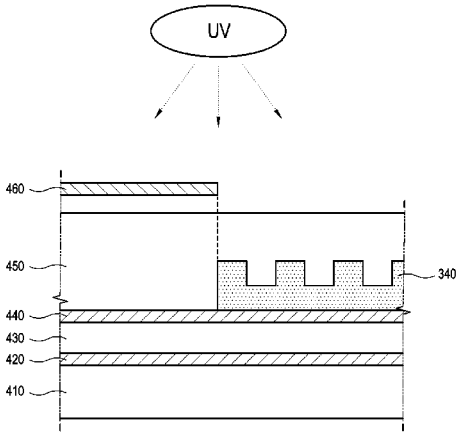
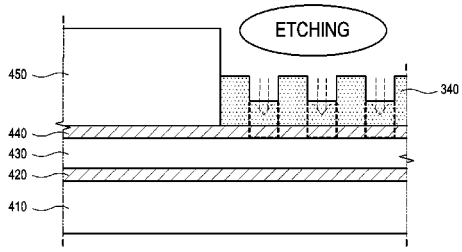
(57) **ABSTRACT**

A method of manufacturing a linear grid for a display panel, the method including: applying a material layer for the linear grid to a substrate; laminating a negative photoresist layer having a pattern of the linear grid to a target area within an entire area of the material layer; laminating a positive photoresist layer to the entire area of the material layer; covering, with a mask for blocking ultraviolet light, areas within the entire area not including the target area, and emitting the ultraviolet light; etching the material layer according to the negative photoresist layer exposed by the ultraviolet light; and forming the pattern of the linear grid on the material layer by removing the negative photoresist layer and the positive photoresist layer from the entire area.

20 Claims, 18 Drawing Sheets